Q. Metrology, Inspection, and Yield Enhancement 분과

2019년 2월 15일(금), 11:00-12:30
Room K (국실, 5층)

[FK2-Q] Metrology, Inspection, and Yield Enhancement

좌장: 조용재 책임연구원(KRISS), 김진승 교수(전북대학교)

FK2-Q-1 **11:00-11:15**	**Discrete Scanning Based TSOM Image Generation and Measurement** Youngback Kim, Junhee Jeong, and Joonghwee Cho *Department of Embedded Systems Engineering, Incheon National University*
FK2-Q-2 **11:15-11:45**	**[초청]** **Automated Inline AFM Solutions for Semiconductor Industry** Sang-Joon Cho[1], Byung-Woon Ahn[1], Tae-Gon Kim[2,3], and Sang-il Park[1] *[1]Park Systems Corp, [2]Department of Materials Science and Chemical Engineering, Hanyang University ERICA, [3]Imec vzw, Leuven, Belgium*
FK2-Q-3 **11:45-12:00**	**The Enhancement to Estimate the Yield Impact of Unknown Defects in the Advanced Technology Node Using Volume Diagnostics** Jeongsu Park, Seungjin Yang, and Brad Kim *Synopsys Korea*
FK2-Q-4 **12:00-12:15**	**A Study on a Near-Field Microscope with Dark-Field Illumination to Detect Defects on Semiconductor Wafer** Woojun Han[1], Hankyung Oh[1], Jaisoon Kim[1], and Yoonki Lee[2] *[1]Department of Physics, Myongji University, [2]AUROS Technology*
FK2-Q-5 **12:15-12:30**	**Critical Nanotopography Metrology Study for Good CMP Process Control and Electical Bonding Yield in Wafer-To-Wafer Hybrid Bonding** Tae-Gon Kim[1,2], Soon-Wook Kim[1], Heon-Yul Ryu[2], Nancy Heylen[1], Ferenc Fodor[1], Dimitrios Velenis[1], Tom Vandeweyer[1], Sang-Joon Cho[1], Sang-il Park[1], Jin-Goo Park[2], and Eric Beyne[1] *[1]Imec vzw, Belgium, [2]Department of Materials Science and Chemical Engineering, Hanyang University ERICA, [3]Park Systems*